## Electronic Supplementary Information

## Ionic Liquid Thin Layer-Induced Memory Effects in Organic Field-Effect Transistors

Keitaro Eguchi,\*† Michio M. Matsushita and Kunio Awaga\*

Department of Chemistry and Integrated Research Consortium on Chemical Science (IRCCS), Nagoya University, Furo-cho, Chikusa-ku, Nagoya 464-8602, Japan

\* E-mail: keitaro.eguchi@tum.de (KE), awaga.kunio@b.mbox.nagoya-u.ac.jp (KA)

Corresponding author Kunio Awaga Department of Chemistry, Nagoya University Furo-cho, Chikusa-ku Nagoya 464-8602, Japan E-mail: Awaga.kunio@b.mbox.nagoya-u.ac.jp Tel: +81-52-789-2487 Fax: +81-52-789-2484

## Contents

- Fig. S1. Sample preparations and *in situ* FET measurements under ultrahigh vacuum conditions.
- Fig. S2. Topological and phase images of thin films of fullerene on 5 ML DEME-TFSI.
- Fig. S3. Topological and phase images of DEME-TFSI on a thin film of pentacene (1.5 ML).
- Fig. S4. Gate leakage current in transfer characteristics of the pentacene FETs without/with the DEME–TFSI layers.
- Fig. S5. Extraction of parameters of  $\mu_{\text{FET}}$ ,  $I_{\text{F}}/I_{\text{R}}$ , and  $\Delta V_{\text{th}}$  from the transfer characteristics.
- Fig. S6. Integrated values of  $|I_{DS}(F)|$  and  $|I_{DS}(R)|$  and their differences.
- Fig. S7. Transfer characteristics of (a) pentacene (IL: 2 ML) and (b) C<sub>60</sub> (IL: 1.5 ML) devices for three cycles.
- Fig. S8. Transfer characteristics of the pentacene and fullerene FETs with the DEME-TFSI layers measured at different  $V_{DS}$ .



Figure S1. Sample preparation and *in situ* FET measurements under high vacuum conditions (base pressure of  $5 \times 10^{-5}$  Pa). DEME-TFSI, pentacene, and fullerene were deposited onto the FET substrates with deposition rates of ~0.2 ML min<sup>-1</sup> for DEME-TFSI and pentacene, and of ~0.4 ML min<sup>-1</sup> for fullerene, using thickness monitors.



Figure S2. Topological AFM image (left) and the corresponding phase image (right) of a fullerene thin film (20 ML), prepared on 5 ML DEME–TFSI. The area shown in the images, is  $1 \times 1 \mu m^2$ .



Figure S3. Topological AFM image (left) and the corresponding phase image (right) of DEME–TFSI deposited on a pentacene thin film (1.5 ML) prepared on a bare SiO<sub>2</sub> surface. The area shown in the images, is  $3 \times 3 \mu m^2$ .



Figure S4. Gate leakage current ( $I_G$ ) in the transfer characteristics of the pentacene FETs with (a) 0 ML, (b) 1 ML, (c) 2 ML, and (d) 5 ML DEME–TFSI, measured at  $V_{DS} = -20$  V in the dark.



Figure S5. Extraction of the field-effect mobility ( $\mu_{\text{FET}}$ ), memory-ratio ( $I_{\text{F}}/I_{\text{R}}$ ), and memory-window ( $\Delta V_{\text{th}}$ ) parameters from the transfer characteristics. The  $\mu_{\text{FET}}$  and  $V_{\text{th}}$  values were calculated with the standard equation in the linear regime,  $I_{\text{DS}} = (W/L)\mu_{\text{FET}}C_iV_{\text{DS}}(V_{\text{G}} - V_{\text{th}} - V_{\text{DS}}/2)$ , described in K. Hagen, *Chem. Soc. Rev.* **39**, 2643–2666, 2010, where  $C_i$  is the capacitance per unit area of the insulating layer.



Figure S6. Integrated values of  $|I_{DS}(F)|$  and  $|I_{DS}(R)|$  and their differences calculated for the pentacene (black) and C<sub>60</sub> (red) FETs with DEME-TFSI layers, using equation (2) in the main text.



Figure S7. Transfer characteristics of (a) pentacene (IL: 2 ML) and (b)  $C_{60}$  (IL: 1.5 ML) devices for three cycles.



Figure S8. Transfer characteristics of (a) pentacene and (b)  $C_{60}$  FETs with 1 ML DEME-TFSI, measured at (a)  $V_{DS} = 0$ , -10, -20, and -30 V and (b)  $V_{DS} = 0$ , +10, +20, and +30 V.